UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/586,187	07/31/2007	Toru Kimura	01115_1013	4887
30671 7590 01/05/2011 DITTHAVONG MORI & STEINER, P.C. 918 Prince Street			EXAMINER	
			JOHNSON, CONNIE P	
Alexandria, VA 22314		ART UNIT	PAPER NUMBER	
			1722	
			NOTIFICATION DATE	DELIVERY MODE
			01/05/2011	ELECTRONIC

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

docket@dcpatent.com

	Application No.	Applicant(s)	
	10/586,187	KIMURA ET AL.	
Office Action Summary	Examiner	Art Unit	
	CONNIE P. JOHNSON	1722	
The MAILING DATE of this communication a Period for Reply	ppears on the cover sheet wit	n the correspondence address	
A SHORTENED STATUTORY PERIOD FOR REF WHICHEVER IS LONGER, FROM THE MAILING - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication If NO period for reply is specified above, the maximum statutory peric - Failure to reply within the set or extended period for reply will, by stat Any reply received by the Office later than three months after the mai earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNIC 1.136(a). In no event, however, may a re- port will apply and will expire SIX (6) MONT ute, cause the application to become ABA	ATION. oly be timely filed HS from the mailing date of this communication. NDONED (35 U.S.C. § 133).	
Status			
Responsive to communication(s) filed on <u>03</u> 2a) This action is FINAL . 2b) ▼ The sum of the practice under the practi	nis action is non-final. vance except for formal matte	·	
Disposition of Claims			
4) ☑ Claim(s) 1-14 is/are pending in the application 4a) Of the above claim(s) is/are withdress 5) ☐ Claim(s) is/are allowed. 6) ☑ Claim(s) 1,9 and 12-14 is/are rejected. 7) ☑ Claim(s) 2-8,10 and 11 is/are objected to. 8) ☐ Claim(s) are subject to restriction and	rawn from consideration.		
<u> </u>			
9) The specification is objected to by the Exami 10) The drawing(s) filed on is/are: a) a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correctable. 11) The oath or declaration is objected to by the	ccepted or b) objected to be ne drawing(s) be held in abeyand ection is required if the drawing(s	e. See 37 CFR 1.85(a). i) is objected to. See 37 CFR 1.121(d)).
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the priority docume application from the International Bure * See the attached detailed Office action for a limit	ents have been received. ents have been received in Apriority documents have been reau (PCT Rule 17.2(a)).	plication No eceived in this National Stage	
Attachment(s) 1) Motice of References Cited (PTO-892)		ımmary (PTO-413)	
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)	/Mail Date ormal Patent Application	

Application/Control Number: 10/586,187 Page 2

Art Unit: 1722

DETAILED ACTION

Response to Amendment

- Applicant's request for reconsideration of the finality of the rejection of the last
 Office action is persuasive and, therefore, the finality of that action is withdrawn.
- 2. The remarks and amendment filed 12/3/2010 have been entered and fully considered.
- 3. Claims 1-14 are presented.
- 4. Claim 7 is amended.

Claim Rejections - 35 USC § 103

- 5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 6. Claims 1, 9, 12, 13 and 14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Miyake et al., U.S. Patent Publication No. 2002/0136979 A1 in view of Endo et al., U.S. Patent Publication No. 2004/0224525 A1.

Miyake teaches a resist material on a substrate with an upper and lower recording layer. The upper recording layer comprises an alkali-soluble resin (page 9, [0087]). The upper recording layer may also comprise a solvent (page 16, [0190-0191]). The solvents comprise propanol, which is a monovalent solvent with 6 or less carbon atoms as in instant claim 13 (page 16, [0082]). Therefore, the components of the upper

Art Unit: 1722

recording layer would not cause intermixing with the photoresist film. With regards to the recitation in claim 1, "for being applied to coat on a photoresist film when using an immersion exposure device which is irradiated through water provided between a lens and the photoresist film...being dissolved in a subsequent developer" is a product by process limitation. Product by process claims are not limited to the manipulations of recited steps, only the structure implied by the steps. "[E]ven though product-byprocess claims are limited by and defined by the process, determination of patentability is based on the product itself. The patentability of a product does not depend on its method of production. If the product in the product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior product was made by a different process." In re Thorpe, 777 F.2d 695, 698, 227 USPQ 964, 966 (Fed. Cir. 1985) (MPEP 2113). The recitation, "forming a water-stable film during irradiation" is intended use and does not add positive recitation to the claim. The recitation in claim 9, "dissolving an alkaline solution during development using the alkaline aqueous solution" is intended use and does not add positive recitation to the claim. Mivake teaches a patter-forming method. However, Mivake does not teach forming a pattern by immersion exposure with water.

Additionally, Endo teaches an immersion exposure method for a resist wherein the resist material is on a substrate and comprises a resist layer and a topcoat layer. The pattern is formed by exposing the resist material to irradiation wherein water is used as the immersion fluid on top of the topcoat layer. The resist is developed to form the pattern (pages 2-3, [0033-0035]). It would have been obvious to one of ordinary skill in

Application/Control Number: 10/586,187 Page 4

Art Unit: 1722

the art to use immersion exposure in the composition of Miyake because immersion exposure is well known to improve resolution of the pattern (page 1, [0003]).

Response to Arguments

7. Applicant's arguments filed 12/3/2010, with respect to the rejection(s) of claim(s) 1-4 and 9 under 102(e) over Li and claims 1, 3 and 5-12 under 103(a) over Li have been fully considered and are persuasive. Therefore, the rejections have been withdrawn.

8. Claims 2-8, 10 and 11 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to CONNIE P. JOHNSON whose telephone number is (571)272-7758. The examiner can normally be reached on 7:30am-4:00pm Monday thru Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Application/Control Number: 10/586,187 Page 5

Art Unit: 1722

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Connie P. Johnson Examiner Art Unit 1795

/Shean C Wu/ Primary Examiner, Art Unit 1722